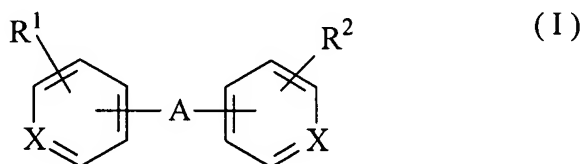


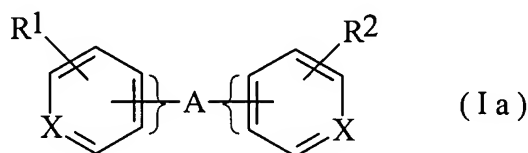
AMENDMENTS TO THE CLAIMS

1. (Currently amended) A negative type resist composition comprising ~~alkali-soluble resin, polyvinyl phenol-based resin in which the phenolic hydroxyl group is partially alkyl-etherified,~~ acid generator, crosslinking agent, and a basic compound represented by the following formula (I)



wherein, A represents sulfide group, disulfide group or bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, [sulfide group, or disulfide group,] X represents nitrogen atom ~~or C(NH₂)~~, and R¹ and R² independently represent hydrogen or alkyl ~~provided that, when X represents C(NH₂), A represents sulfide group or disulfide group.~~

2. (Original) The negative type resist composition according to claim 1, wherein the basic compound of the formula (I) is represented by the following formula (Ia):



wherein, A, X, R¹ and R² are the same as defined in claim 1, and the marks, "}" and "{", indicate that A is positioned on 3-position, or 4-position on the six-membered rings with respect to X.

3. (Canceled)

4. (Canceled)

5. (Currently amended) The negative type resist composition according to ~~claim 4~~ claim 1, wherein the basic compound of formula ~~(Hb)~~ (I) is selected from 1,2-di(4-pyridyl)ethane, 1,3-di(4-pyridyl)propane, 1,2-di(4-pyridyl)ethylene and bis(3-pyridylmethyl)amine.

6. (Canceled)

7. (Currently amended) The negative type resist composition according to ~~claim 6~~ claim 1, wherein the basic compound of formula ~~(Hb)~~ (I) is selected from 4,4'-dipyridylsulfide and 4,4'-dipyridyldisulfide.

8. (Canceled)

9. (Previously presented) The negative type resist composition according to claim 1, wherein the acid generator is a sulfonic ester of N-hydroxyimide compound.

10. (Original) The negative type resist composition according to claim 1, wherein composition ratio of the basic compound of formula (I) is between 0.02 and 1 wt %, based on the total solid content in the composition.

11. (Original) The negative type resist composition according to claim 1, wherein A is a linear alkylene having 2 to 4 carbon atoms, linear alkenylene having 2 to 4 carbon atoms or iminobisalkylene having 2 to 6 carbon atoms.

12. (Original) The negative type resist composition according to claim 1, wherein A is a sulfide group or a disulfide group.

13. (Original) The negative type resist composition according to claim 1, wherein A is selected from the group consisting of methylene, ethylene, vinylene, trimethylene, tetramethylene, iminobismethylene, sulfide and disulfide.